What is claimed is:

- 1. A method for verifying reticle enhancement technique latent image sensitivity to mask manufacturing errors, said method comprising: revising a polygon based on mask CD distributions to provide a virtual statistical mask; obtaining response function statistical parameters based on the virtual mask image; and comparing the statistical parameters to design rule requirements.
- 2. A method as recited in claim 1, further comprising forming an simulated image of the virtual mask.
- 3. A method as recited in claim 2, further comprising calculating response functions based on the aerial and/or latent image simulation.
- 4. A method as recited in claim 3, further comprising collecting measurements and calculating statistical parameters based on the response functions.
 - 5. A method as recited in claim 4, further comprising comparing the statistical parameters with design rule requirements.

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- 6. A method as recited in claim 1, further comprising obtaining the virtual mask by using mask CD distribution to induce statistical variations to layouts which have passed through an OPC procedure.
- 7. A method as recited in claim 6, further comprising at least one of moving fragments of a polygon and re-sizing primitives.

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- 8. A method as recited in claim 6, further comprising moving fragments of a polygon based on a randomly generated number from mask CD distribution.
- 9. A method as recited in claim 6, further comprising re-sizing primitives depending on mask CD distribution.
- 10. A yield prediction tool for mask quality specifications, said tool comprising means for revising a polygon based on mask CD distributions to provide a virtual mask, means for obtaining statistical parameters based on the virtual mask imaging; and means for comparing the statistical parameters to design rule requirements
- 11. A tool as recited in claim 10, further comprising means for simulating an aerial20 and/or latent image of the virtual mask.

- 12. A tool as recited in claim 11, further comprising means for calculating response functions based on the simulated image.
- 13. A tool as recited in claim 12, further comprising means for collecting measurements and calculating statistical parameters based on the response functions.
- 14. A tool as recited in claim 13, further comprising means for comparing the statistical parameters with design rule requirements.
- 15. A tool as recited in claim 10, further comprising means for obtaining the virtual mask by using mask CD distribution to statistically vary layouts which have passed through an OPC procedure.
- 16. A tool as recited in claim 15, further comprising means for at least one of moving fragments of a polygon and re-sizing primitives.
 - 17. A tool as recited in claim 15, further comprising means for moving fragments of a polygon based on a randomly generated number from mask CD distribution.

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18. A tool as recited in claim 15, further comprising means for re-sizing primitives depending on mask CD distribution.